	Hits	Search Text	DBs
1		(organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near antireflecti\$3) same etch\$3 same (((hydrogen H2 "H.sub.2" H2O "H.sub.2" o") and (N2 "N.sub.2" nitrogen)) NH3 "NHsub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
2	39	((organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near antireflecti\$3) same etch\$3 same (((hydrogen H2 "H.sub.2" H2O "H.sub.2 O") and (N2 "N.sub.2" nitrogen)) NH3 "NHsub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)) and ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen))	IBM_TDB
3	12	etch with (organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near antireflecti\$3) same ((hydrogen H2 "H.sub.2")with (N2 "N.sub.2" nitrogen))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
4	27	(((organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near antireflecti\$3) same etch\$3 same (((hydrogen H2 "H.sub.2" H2O "H.sub.2 O") and (N2 "N.sub.2" nitrogen)) NH3 "NHsub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)) and ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen))) not (etch with (organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near antireflecti\$3) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
5	1 3	etch with (organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near antireflecti\$3) same (NH3 "NH.sub.3" ammonia)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB